

Coating of $\text{TiO}_2/\text{SiO}_2$ thin films on particles
prepared by PCVD reactor

Pham Hung Cuong, 김교선*

강원대학교

(kkyoseon@kangwon.ac.kr*)

We coated thin films on particles using a rotating PCVD reactor and examined the effects of various process variables on the growth and characteristics of thin films on the particles. The morphologies and cross-sectional views of the films were analyzed by SEM. We obtained the film thicknesses coated on the particles from SEM measurements for various process conditions. The thin films grew more quickly on the particles with increasing mass flow rate of precursor, deposition time, or rotation speed of the reactor.